## Direct response time measurements on semiconductor (& metal?!) photocathodes

Measuring bunch lengthening during the photoemission process

Gregor Loisch on behalf of the PITZ & INFN Milano cathode groups

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## **Cathode response time measurements**

Delay time of emitted electrons from semiconductors

- *"Spicer* 3-step model": Excitation, Transport, Emission
- Incident photon releases electron from cathode
- Varying delay until electron extraction
  - Penetration depth of photon
  - > Path of electron in cathode (collision with phonons if  $E < E_{exc}$ )
- Smears out electron bunch time profile
  - Defines achievable accuracy of bunch shaping
  - Defines minimum bunch length
  - Allows to confirm emission model
  - Data on "green" cathodes needed
  - Literature data on e.g. Cs2Te not satisfying



Response time definition here:

Characteristic time scale of cathode contribution to bunch length

## **Results in literature**

#### Measurement methods and results

- Direct measurement of Cs3Sb resp. time
  - Low resolution (~2ps)  $\rightarrow$  only upper limit
- No direct measurement of response time in RFaccelerator reported for Cs2Te
  - Measurement with streak camera
- Measurement/"estimation" by measuring minimum separation between 2 short bunches in energy spectrum
  - "P2P RMS separation" of ~370 fs
- Monte-Carlo simulations
- $\rightarrow$  Expected Cs2Te cathode response shape: exponential & ~x00 fs scale
- $\rightarrow$  No direct measurement so far



3000

2500 

2000

1500

500

Transit time (fs)

Emitted 1000

Cultrera et al. – APL 99, 152110 (2011)

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double gauss fit

Aryshev et al. - APL 111, 033508 (2017)



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## **Measurement setup**

#### The PITZ facility

- Measure bunch length of low charge, short bunch with high resolution TDS
- Identify RF-contribution to bunch length via two bunch probe beam
- Disentangle cathode response from laser shape
   → laser ~Gaussian, ~170fs RMS

#### Procedure:

- Measure double bunch time structure for
  - Different charges
  - Different gradients
- Disentangle rf compression from signal
  - → direct calibration to "laser time"



## **Error mitigation**

#### Identify and avoid several sources of systematic errors

- Several error sources identified
  - x-y-correlations
  - bunch z-y-correlations
  - bunch pair z-y-correlations
  - laser pulse time delay calibration
  - statistical
  - space charge induced lengthening

- Error mitigation includes
  - avoiding x-y-correlations
  - averaging over different TDS slopes
  - averaging over different laser pulse "chronological" orders
  - high statistics
  - low bunch charge, large cathode laser spot



## **ASTRA simulations & error estimation**

#### Start to end simulation of measurements

- Simulated beam transport of exponential response time in ASTRA
- S2E simulation of full measurement
- Resp. time error much lower than RMS bunch length measurement
- Simulated resp. time error <2.5% !!</p>
- Additional laser stage positioning error ~5%
- $\rightarrow$  Main error source: signal to noise ratio





## **Cs2Te response time**

#### **Measurement results for Cs2Te**

- Convoluted exponential Gaussian long. bunch shape
- ► Bunch charge scan → no space charge influence
- Measured various Cs2Te cathodes
- Shortest measured resp. time: 184 ± 42 fs
- Longest measured resp. time: 257 ± 41 fs
- ► Gaussian RMS length ~185 fs → reasonable agreement w/ laser transform limit ~170 fs
- Transient grating measurement of laser pulse length ~113 ± 7 fs (~130fs incl. res./disp.)
   → discrepancy to be resolved (see below..)



 $(1.02 \pm 0.49) \, pC$ 

## **Simulations**

#### Modelling excitation & transport in the cathode

- 1-to-1 photoemission modeling based on Spicer's three-step model
- Initial electron exciting conditions based on density of states
- Electron-phonon scattering; mean free path 3 nm (literature data, INFN)
- Ionization energy @ room temperature
- Emission angle dependency



10 simulations, MFP = 3 nm,  $\Delta E$  = 8 meV

## **Summarised measurements**

#### Information gathered so far

- Errors contain statistical variation and systematic uncertainty
- No aging effect on cathode response time
- ► INFN & DESY cathodes inconsistent → similar production procedure!?!
- No QE dependence found in either cathode batch
- Cs2Te thickness studies not conclusive
   → more measurements and cathodes to come





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## **CsKSb** measurement

First response time for CsKSb cathode

- Cathode prepared at INFN Milano
- Measurement @PITZ after several hours of cathode usage
  2.5% > 0.4%
  - → QE had dropped:  $\sim 2.5\% \rightarrow \sim 0.4\%$
- Measured exp. component < 100 fs</p>
- Unexpectedly short, ~measuring degraded surface layer?
- Repeat w/ fresh cathode...



Cath. 147.1

### **Reference measurements**

#### Measured Mo & Au cathodes as reference

- Mo and Au cathodes gave similar results
- ~Gaussian bunch shape
- RMS lengths of 237 fs 271 fs (±50 fs)
  - Ionger than Gaussian w/ Cs2Te
  - >> laser pulse length
- Mo not polished, found production error for Au cathode
- ► new Au cathode was measured: 183 ± 10 fs → Gaussian lengthening much reduced
- Fitted exp. time constant: 93 ± 17 fs
   → similar error as Gaussian fit → resolution limit
- Systematic studies missing..



## **Summary**

#### Status and possible future studies

- First time Cs2Te cathode response directly measured
- Measurement procedure established & in routine usage (>~45 fs RMS symmetric resolution)
- Cs2Te cathode exponential response time ~185-257 fs (depending on cathode)
- Emission process simulation results show reasonable agreement
- $\blacktriangleright$  Measured metal response ~too slow  $\rightarrow$  possibly roughness, systematic studies needed
- INFN Milano & DESY cathodes consistently different (similar production procedure..)
- Available & future data could enable/inform advanced cathode preparation
  - Deposition techniques

• ....

- Other materials (CsKSb...)
- Cathode thicknesses / Minimum achievable response time

# Thank you for your attention!

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#### Direct measurement of photocathode time response in a high-brightness photoinjector

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Gregor Loisch,<sup>1,4,b)</sup> <sup>(6)</sup> Ye Chen,<sup>2,b)</sup> <sup>(6)</sup> Christian Koschitzki,<sup>1</sup> Houjun Qian,<sup>1</sup> Matthias Gross,<sup>1</sup> <sup>(6)</sup> Adrian Hannah,<sup>3</sup> Andreas Hoffmann,<sup>1</sup> Davit Kalantaryan,<sup>1</sup> <sup>(6)</sup> Mikhail Krasilnikov,<sup>1</sup> Sven Lederer,<sup>2</sup> <sup>(6)</sup> Xiangkun Li,<sup>1</sup> Osip Lishilin,<sup>1</sup> <sup>(6)</sup> David Melkumyan,<sup>1</sup> Laura Monaco,<sup>4</sup> Raffael Niemczyk,<sup>1</sup> <sup>(6)</sup> Anne Oppelt,<sup>1</sup> <sup>(6)</sup> Daniele Sertore,<sup>4</sup> <sup>(6)</sup> Frank Stephan,<sup>1</sup> <sup>(6)</sup> Reza Valizadeh,<sup>6</sup> <sup>(7)</sup> Gryoril Vashchenko, <sup>(6)</sup> <sup>(6)</sup> and Tobias Weilbach<sup>1</sup>

#### AFFILIATIONS

<sup>1</sup>Deutsches Elektronen-Synchrotron DESY, 15738 Zeuthen, Germany <sup>3</sup>Deutsches Elektronen-Synchrotron DESY, 22607 Hamburg, Germany <sup>5</sup>ASTeC, STFC Daresburg Laboratory, Daresburg, Warrington, WA4 4AD Cheshire, United Kingdom <sup>4</sup>Stituto Nazionale di Fisica Nucleare, 20133 Milano, Italy

<sup>a)</sup>Present address: Deutsches Elektronen-Synchrotron DESY, 22607 Hamburg, Germany. <sup>b)</sup>Authors to whom correspondence should be addressed: gregor.loisch@desy.de and ye.lining.chen@desy.de

#### Contact

**DESY.** Deutsches Elektronen-Synchrotron Frank Stephan frank.stephan@desy.de

Gregor Loisch gregor.loisch@desy.de

www.desy.de

Andreas Hoffmann <u>andreas.hoffmann@desy.de</u>

